ABSTRACT

A lithographic apparatus includes a device having a plurality blades, each blade being selectively insertable into the beam of radiation. The device is in a first plane intermediate a second plane conjugate to a plane of the substrate and a third plane conjugate to a pupil plane of the projection system. The blades may include a plurality of partially opaque and solid blades or a plurality of blades having a predetermined transmissibility pattern. The transmissibility may vary in a second direction perpendicular to the first direction in which the substrate and the patterning device are movable relative to each other. In an illumination system including a field faceted mirror and a pupil faceted mirror, the illumination system may include a plurality of reflecting blades selectively insertable into the beam to reflect a portion of the beam to a beam dump. The beam dump may be cooled to reduce a heat load on the apparatus. The reflecting elements may be coated with a coating that scatters the portion of radiation or changes the phase of the portion of radiation.